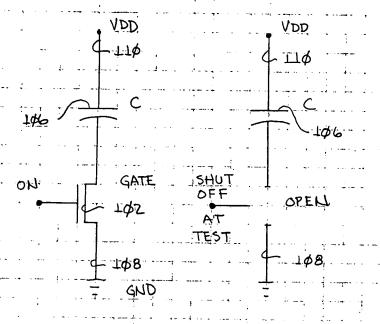


DECOUPLING CAP WITH NEET GATE

PRIOR ART

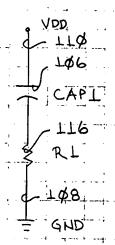
FIG. L

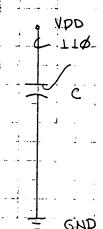


PRIOR ART

FIG. 2

A second second

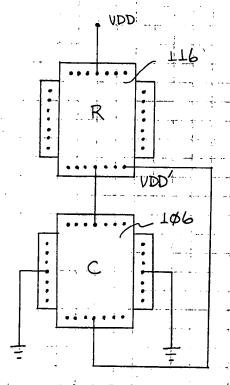


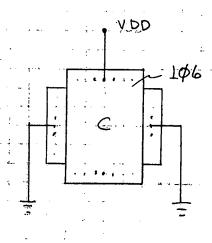


F16. 3

PRIOR ART

DECOUPLING CAP WITH INTERATED RESISTOR





F16.6

PRIOR ART

FIG. 4

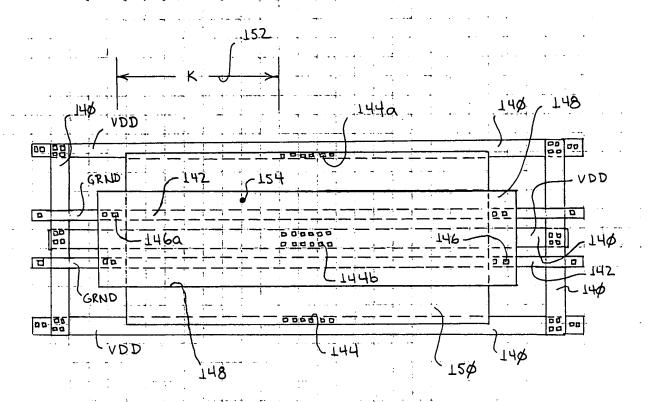


FIG. 7

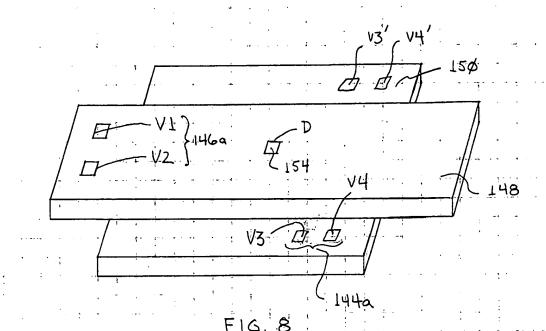
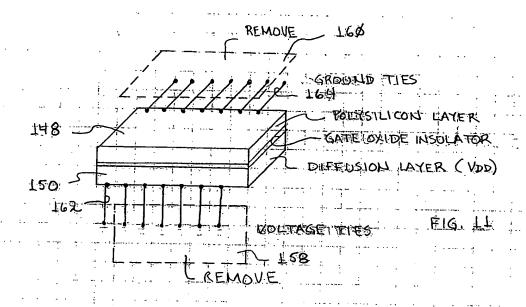
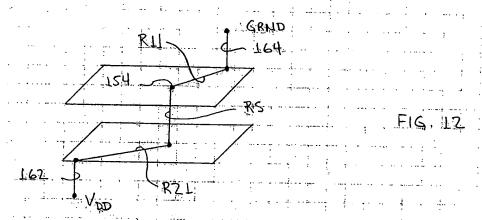
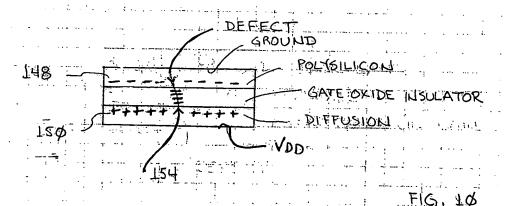
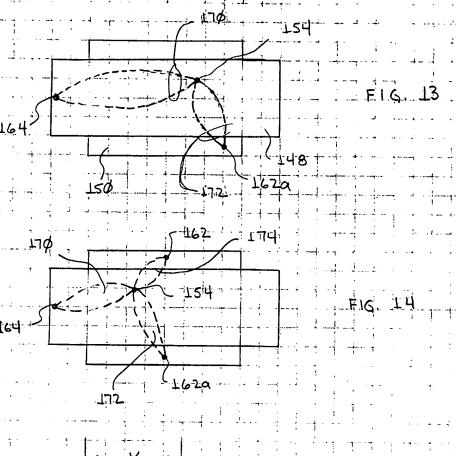


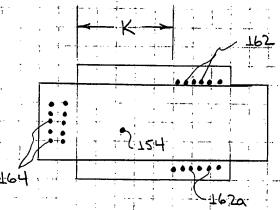
FIG. 9











DETERMINE MAXIMUM ALLOWABLE DEFECT CURRENT! FOR DDQ TESTING DETERMINE MINIMUM SHEET RESISTANCE VALUE IR TO ACHIEVE ALLOWABLE DEFECT CURRENTY DETERMINE MINIMUM DISTANCE K BETWEEN CONTACT SITES TO ACHIEVE SHEET RESISTANCE R DETERMINE HUMBER OF CONTACTS REQUIRED TO PROVIDE, SUFFICIENTLY LOW CONTACT RESISTANCE TO ASSURE SHEET RESISTANCE DOMINATES TOTAL RESISTANCE PROVIDE CONTACT SITES OF SUFFICIENT AREA TO ACCOMMODATE NUMBER OF -CONTACTS, THESE SITES SEPARATED BY AT LEAST K

FIG. 16

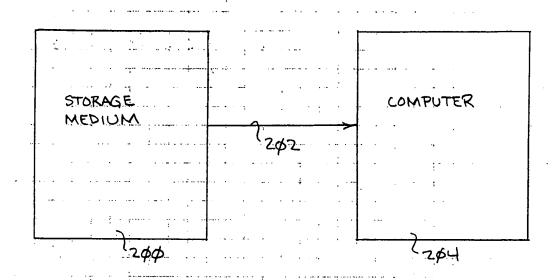


FIG. 17

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